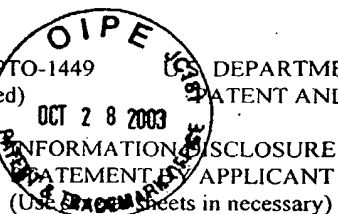


FORM PTO-1449
(Modified)



DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO.: 170239-00046
SERIAL NO.: 10/617,836
APPLICANT: Ji-Guang Zhang
FILING DATE: 07/11/03
ART GROUP:
EXAMINER:
Sheet 1 of 2

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

Examiner Initial		Document No.	Date	Name	Class	Subclass	Filing Date
jr	AA	3,237,078	2/66	H.R. Mallory	320	17	3/14/63
	AB	3,393,355	7/68	P.J. Whoriskey et al	320	18	8/9/65
	AC	4,154,902	5/79	Schwartz	429	15	9/13/76
	AD	4,303,877	12/81	Meinhold	320	18	5/1/79
	AE	4,614,905	9/86	Petersson et al.	320	18	10/10/83
	AF	4,654,281	3/87	Anderman et al.	429	209	3/24/86
	AG	4,719,401	1/88	Altmejd	320	13	12/4/85
	AH	4,996,129	2/91	Tuck	429	194	12/29/88
	AI	5,270,635	12/93	Hoffman et al.	320	21	2/14/92
	AJ	5,291,116	3/94	Feldstein	320	4	9/23/92
	AK	5,314,765	5/94	Bates	429	194	10/14/93
	AL	5,336,573	8/94	Zuckerbrod et al.	429	252	7/20/93
	AM	5,338,625	8/94	Bates et al.	429	193	7/20/92
	AN	5,362,581	11/94	Chang et al.	429	249	4/1/93
	AO	5,387,857	2/95	Honda et al.	320	18	2/7/92
	AP	5,411,592	5/95	Ovsbinsky et al.	118	718	6/6/94
	AQ	5,445,906	8/95	Hobson et al.	429	162	8/3/94
	AR	5,455,126	10/95	Bates et al.	429	127	5/25/94
	AS	5,512,147	4/96	Bates et al.	204	192.15	5/25/94
	AT	5,561,004	10/96	Bates et al.	429	162	2/25/94
	AU	5,567,210	10/96	Bates et al.	29	623.5	7/12/94
	AV	5,569,520	10/96	Bates	429	162	6/7/95
	AW	5,589,291	12/96	Carlin et al.	429	103	2/22/96
	AX	5,597,660	1/97	Bates et al.	429	191	5/25/94
	AY	5,612,152	3/97	Bates	429	152	4/17/96
	AZ	5,654,084	8/97	Egert	428	215	7/22/94
	BA	5,778,515	7/98	Menon	28	623.4	4/11/97
	BB	5,783,928	7/98	Okamura	320	122	4/2/93
	BC	5,811,205	9/98	Andrieu et al.	429	137	12/27/95
jr	BD	5,821,733	10/98	Turnbull	320	116	12/16/96

John Murphy
EXAMINER

9-28-04
DATE

OCT 28 2003
PATENT & TRADEMARK OFFICE

Examiner Initial		Document No.	Date	Name	Class	Subclass	Filing Date
<i>gr</i>	BE	5,932,375	8/99	Tarcy et al.	429	231.95	11/19/97
	BF	6,071,797	6/00	Endo et al.	438	488	9/24/96
	BG	6,197,450	3/01	Nathan et al.	429	236	10/22/98
	BH	6,235,425	5/01	Hanson et al.	429	209	12/12/97

OIPE
OCT 8 2003
PATENT & TRADEMARK OFFICE

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>gr</i>	BI	Journal of Power Sources, P. Fragnaud, R. Nagarajan, D.M. Schleich, D. Vujic, Thin-film cathodes for secondary lithium batteries, 1995 <i>(no month)</i>
	BJ	Materials Research Society, The Preparation and Characterization of Lithium Cobalt Oxide Thin Films by LPCVD, 1996 <i>(no month)</i>
	BK	Journal of Power Sources, Thin film solid electrolytes and electrodes for rechargeable lithium-ion batteries, J. Schoonman, E.M. Kelder, 1997 <i>(no month)</i>
	BL	Solid State Ionics, Fabrication of LiCoO ₂ thin film cathodes for rechargeable lithium battery by electrostatic spray pyrolysis, C.H. Chen et al., 1995 <i>(no month)</i>
	BM	Journal of Materials Science, Unique porous LiCoO ₂ thin layers prepared by electrostatic spray deposition. C.H. Chen et al., 1996 <i>(no month)</i>
	BN	Chemical Congress, Hiroshima, May 1997
	BO	Materials Research Society, Volume 369, 1995, pages 136-147 <i>(no month)</i>
	BP	Reprint from Journal of the Electrochemical Society, Volume 144, No. 2, February 1997
	BQ	Li-Ion Thin-Film Batteries with Tin and Indium Nitride and Subnitride Anodes MeN _x (Me=Sn, In) by B.J. Neudecker and R.A. Zuhr, November 1999
	BR	Solid State Ionics 53-26 (1992) 647-654 North Holland, "Electrical properties of amorphous lithium electrolyte thin films" J.B. Bates et al.
<i>gr</i>	BS	Journal of the Electrochemical Society, 148 (11) A1260-A1265 (2001) "Electrochemical Properties of Carbonaceous Thin Films Prepared by Plasma Chemical Vapor Deposition" Tomokazu Fukutsuka et al. <i>(no month)</i>

EXAMINER <i>John M. ...</i>	DATE CONSIDERED <i>9-28-04</i>
-----------------------------	--------------------------------

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.